

# Progress in fabrication of high quality Tantalum film absorber for STJ radiation detector.



M.P.Lissitski<sup>a,b</sup>, D. Perez de Lara<sup>a,b</sup>, R. Cristiano<sup>a,b</sup>, M.L.Della Rocca<sup>c</sup>, L. Maritato<sup>c</sup>,  
M. Salvato<sup>c</sup>

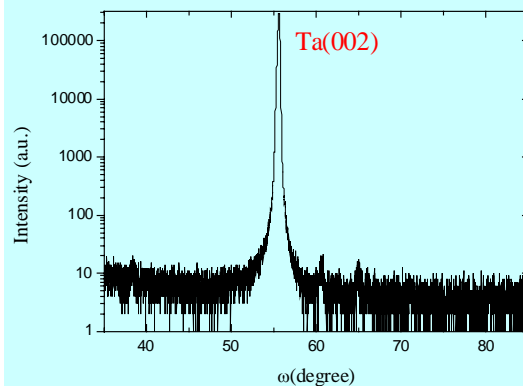
<sup>a</sup>C.N.R. - Istituto di Cibernetica "E.Caianiello", via Campi Flegrei 34, I-80078 Pozzuoli, Napoli, Italy

<sup>b</sup>I.N.F.N., Sezione di Napoli, Complesso Universitario di Monte Sant'Angelo, Via Cintia, I-80126, Napoli, Italy

<sup>c</sup>Dipartimento di Fisica and INFN Università di Salerno, Via S. Allende, I-84081 Baronissi, Salerno, Italy

Deposition methods: magnetically-enhanced dc-triode sputtering  
Substrates: R-plane single crystal sapphire at  $T=800^\circ$

**RRR= 75**  
 **$T_c=4.5 \pm 0.1K$**   
 **$\Delta T_c=0.01K$**



## Ta absorber with lateral Al-STJs

